

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

Applicant	:	Hada et al.
Appl. No.	:	10/535,533
Filed	:	May 19, 2005
For	:	METHOD OF FORMING RESIST PATTER, POSITIVE RESIST COMPOSITION, AND LAYERED PRODUCT
Examiner	:	Chu, John S. Y.
Group Art Unit	:	1752

RESPONSE TO OFFICE ACTION**Mail Stop Amendment**

Commissioner for Patents

P.O. Box 1450

Alexandria, VA 22313-1450

Dear Sir:

In response to the Office Action mailed **March 9, 2007**, please consider the following remarks

Remarks begin on page 2 of this paper.